

1074782
07/14/02
JC4/156

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10047382	FILING DATE 01/14/2002	CLASS 156	SUBCLASS 73	GAU 3770 4760	EXAMINER H. J. K.
----------------------	---------------------------	--------------	----------------	---------------------	----------------------

**APPLICANTS: Sharan Sujit; Sandhu Gurtej; Smith Paul; Chiang Mei;

G. J. K.

**CONTINUING DATA VERIFIED:
THIS APPLICATION IS A DIV OF 09/026,042 02/19/1998

** FOREIGN APPLICATIONS VERIFIED:

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed	<input type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO
35 USC 119 conditions met	<input type="checkbox"/> yes <input type="checkbox"/> no	MI22-1902
Verified and Acknowledged Examiners's initials		

TITLE : RF powered plasma enhanced chemical vapor deposition reactor and methods of effecting
plasma enhanced chemical vapor deposition

U.S. DEPT. OF COMMERCE, THE PATENT & TRADEMARK OFFICE

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING		
Amount Due	Date Paid	Sheets Drawg.	Figs. Drawg.	Print Fig.
TERMINAL DISCLAIMER		Primary Examiner		
		Application Examiner		
PREPARED FOR ISSUE				
WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368. Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.				

FILED WITH:

DISK (CRF)

CD-ROM
(Attached in pocket on right inside flap)